A 1 98102001

Fig 1

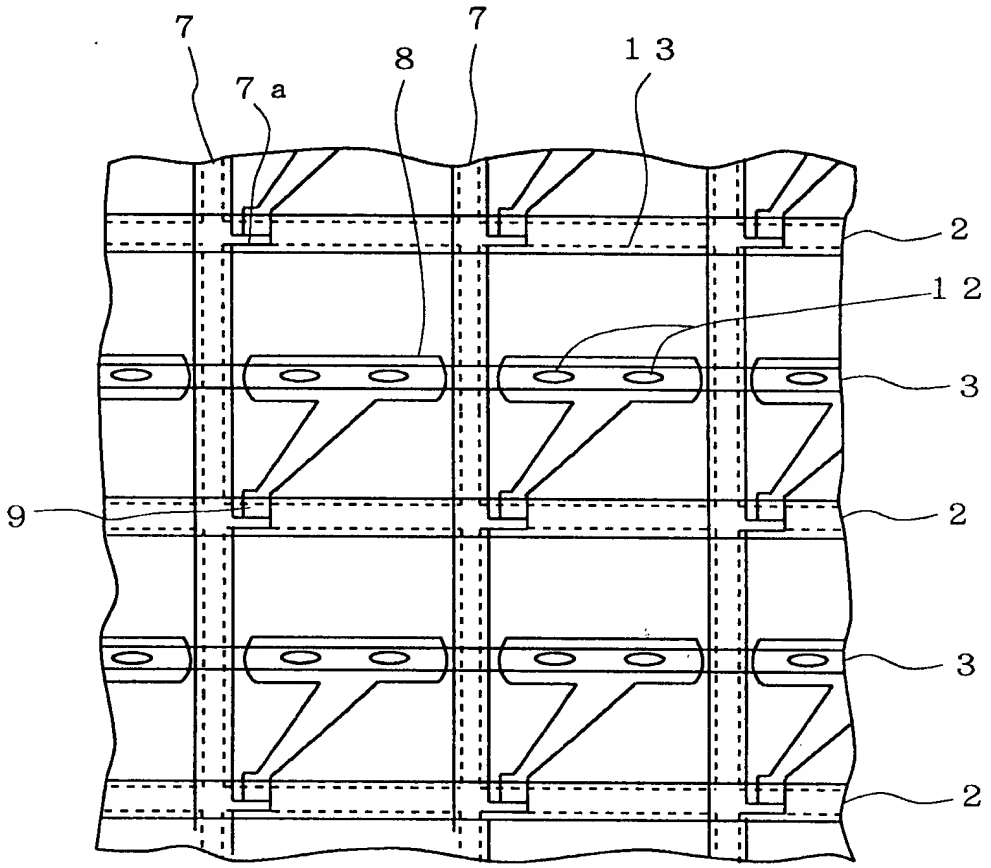
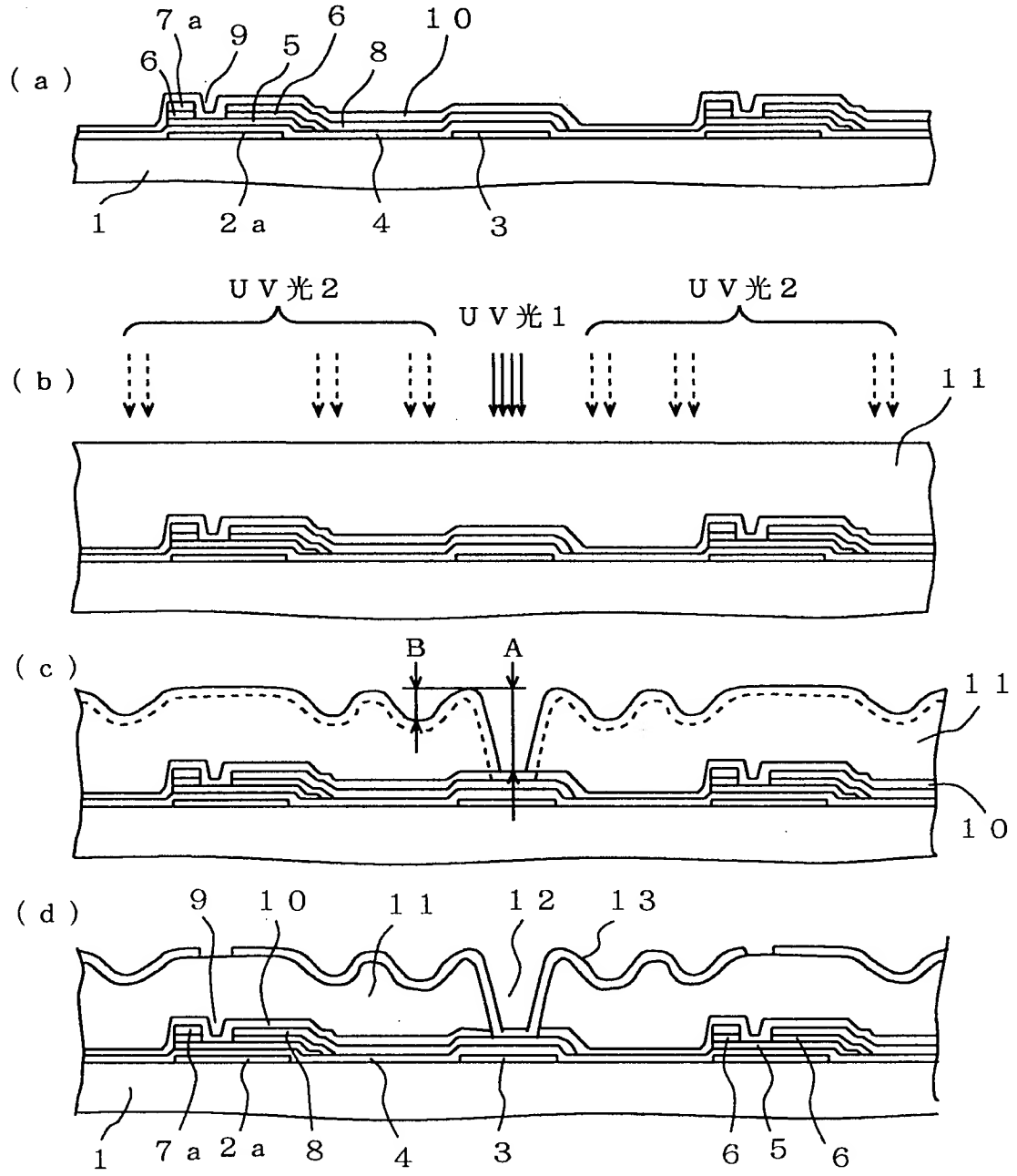


Fig 2



1：絶縁性基板　　6：n^+－a－Si膜　　11：層間絶縁膜
2：ゲート電極配線　　7：ソース電極配線　　12：コンタクトホール
2a：ゲート電極　　7a：ソース電極　　13：反射画素電極
3：共通電極配線　　8：ドレイン電極
4：ゲート絶縁膜　　9：チャネル部
5：a－Si膜　　10：パッシベーション膜

Fig 3

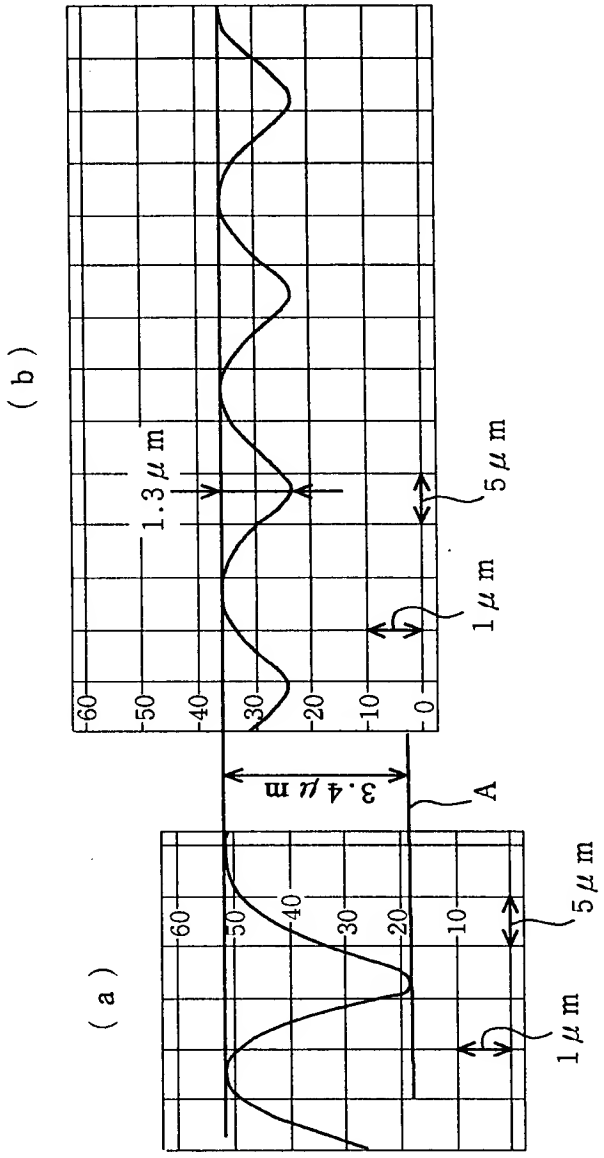


Fig 4

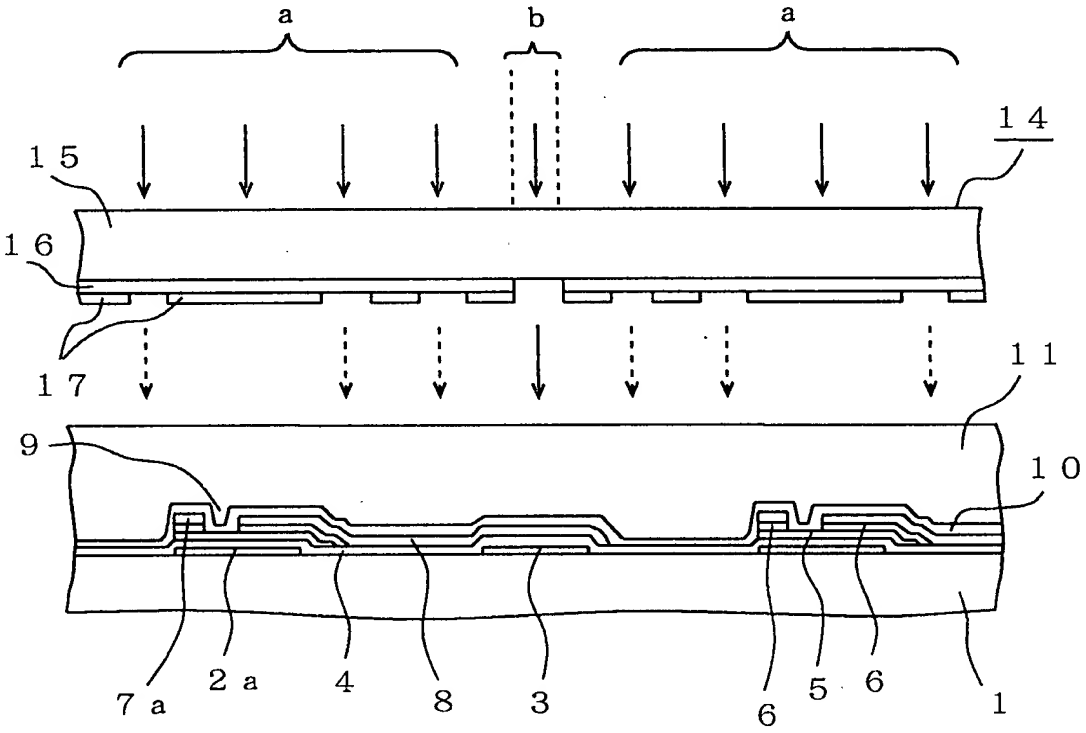
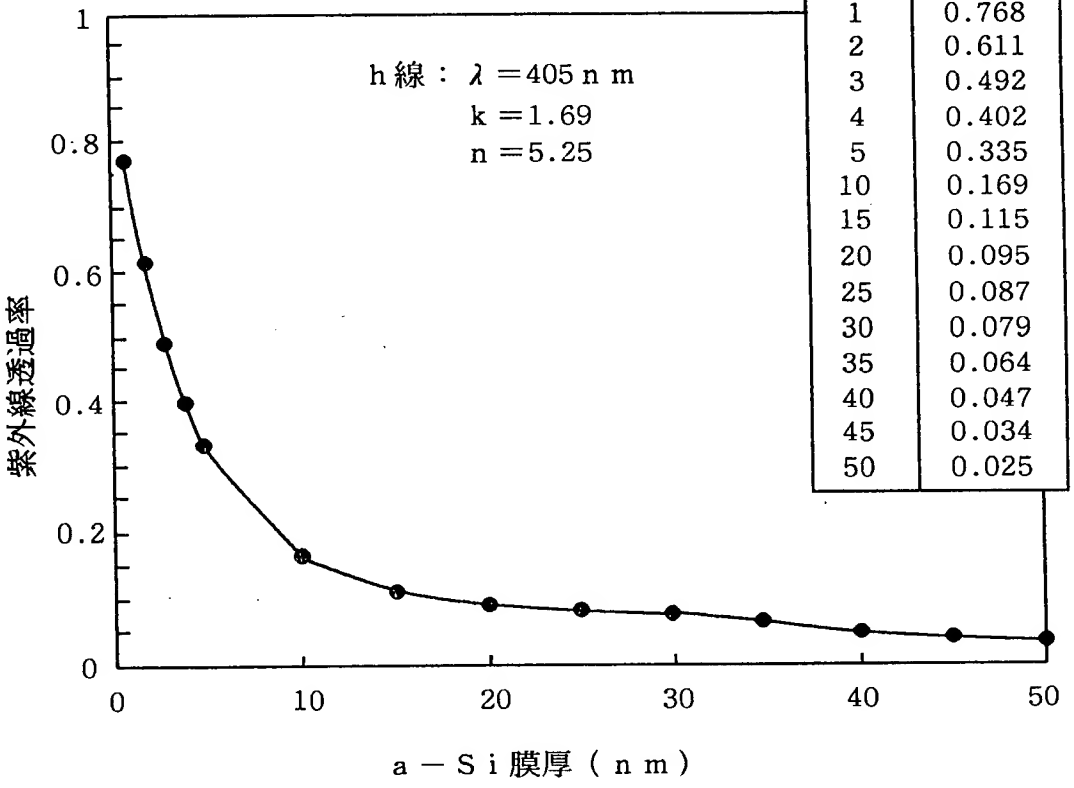


Fig 5



膜厚	透過率
1	0.768
2	0.611
3	0.492
4	0.402
5	0.335
10	0.169
15	0.115
20	0.095
25	0.087
30	0.079
35	0.064
40	0.047
45	0.034
50	0.025

Fig 6

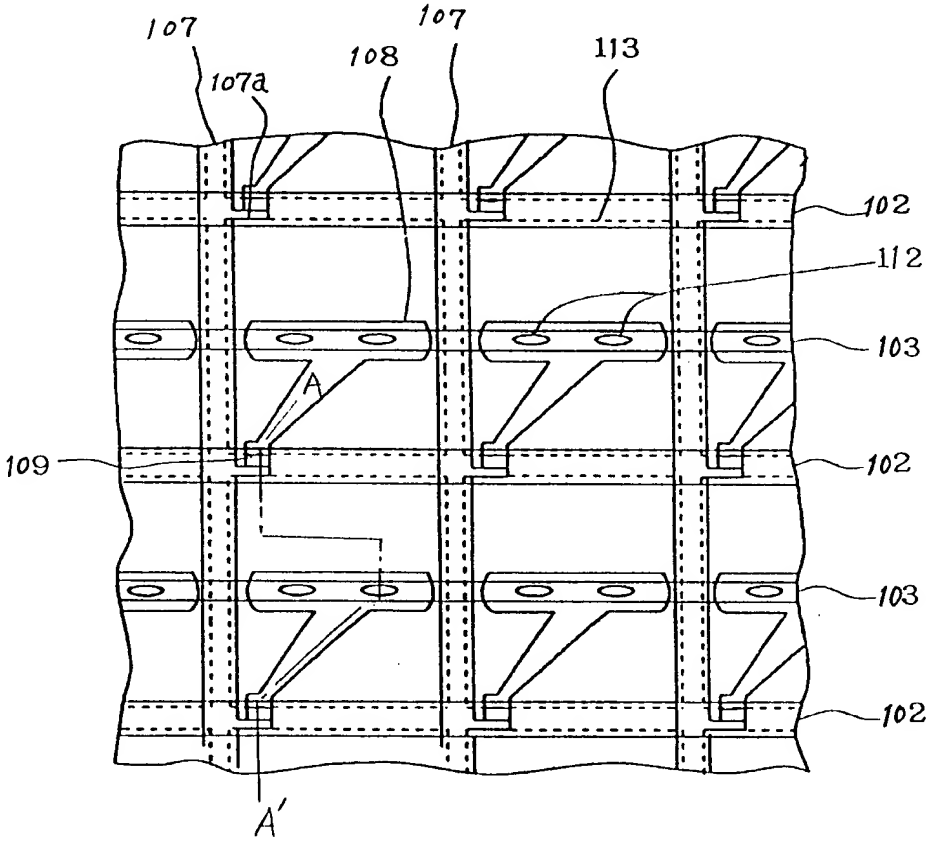
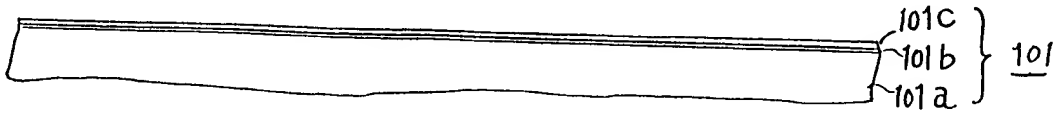
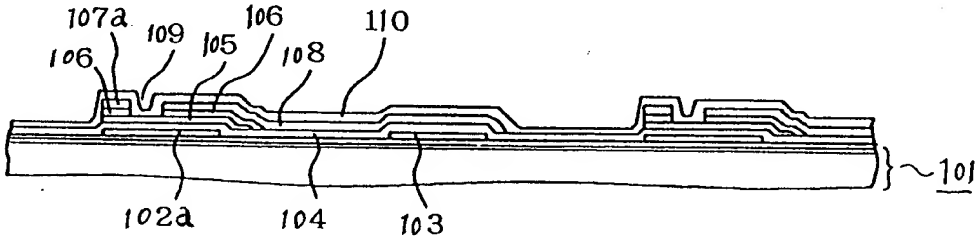


Fig 7

(a)


101c
101b
101a
101

(b)


107a
109
106
105
106
108
110
101
102a
104
103

(c)

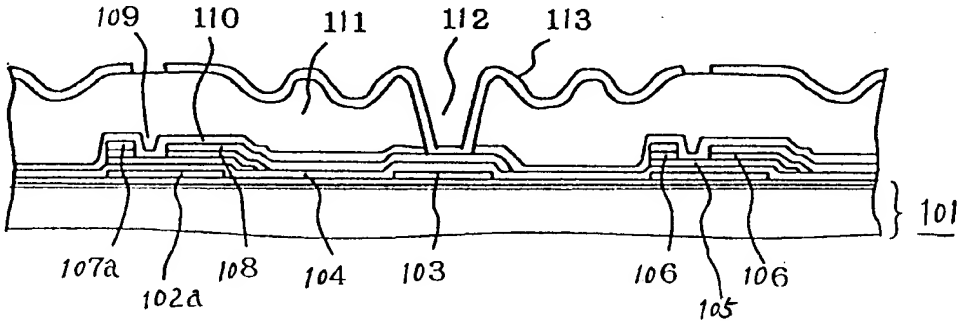
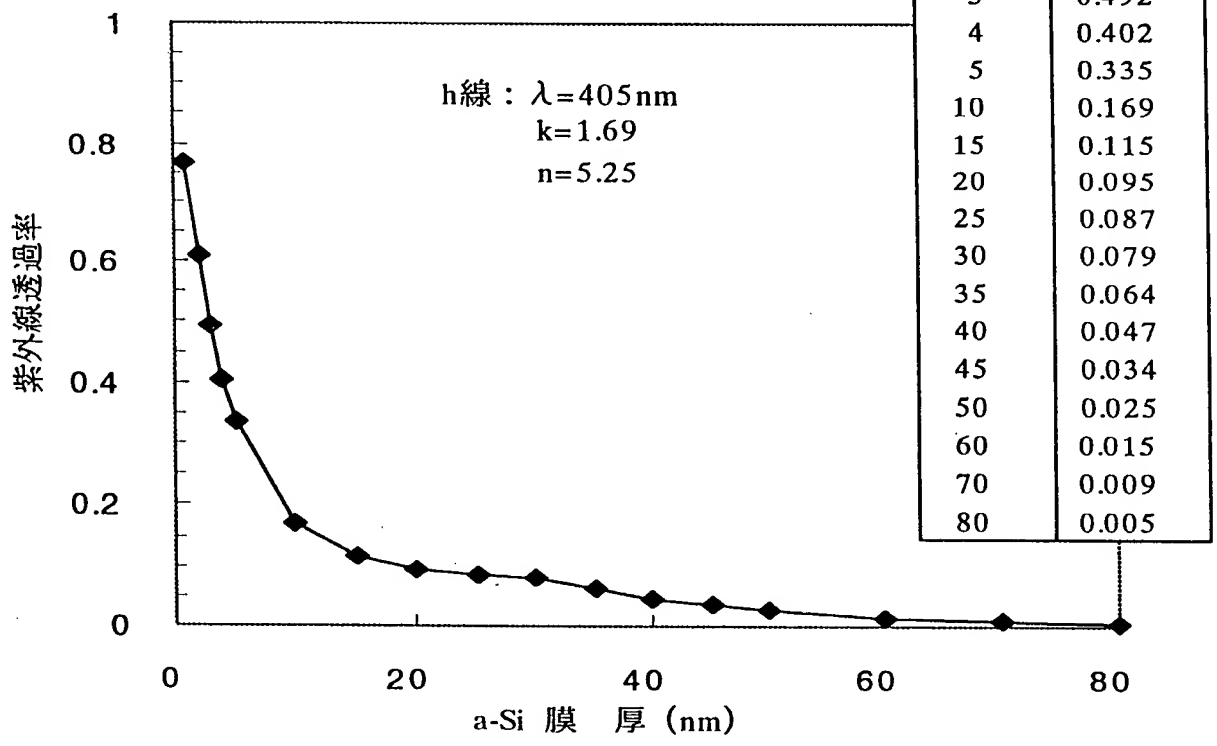

109
110
111
112
113
101
107a
102a
108
104
103
106
105
106

Fig 8



膜厚 nm	透過率
1	0.768
2	0.611
3	0.492
4	0.402
5	0.335
10	0.169
15	0.115
20	0.095
25	0.087
30	0.079
35	0.064
40	0.047
45	0.034
50	0.025
60	0.015
70	0.009
80	0.005

a-Si 膜厚に対する紫外線透過率（計算値）

Fig 9

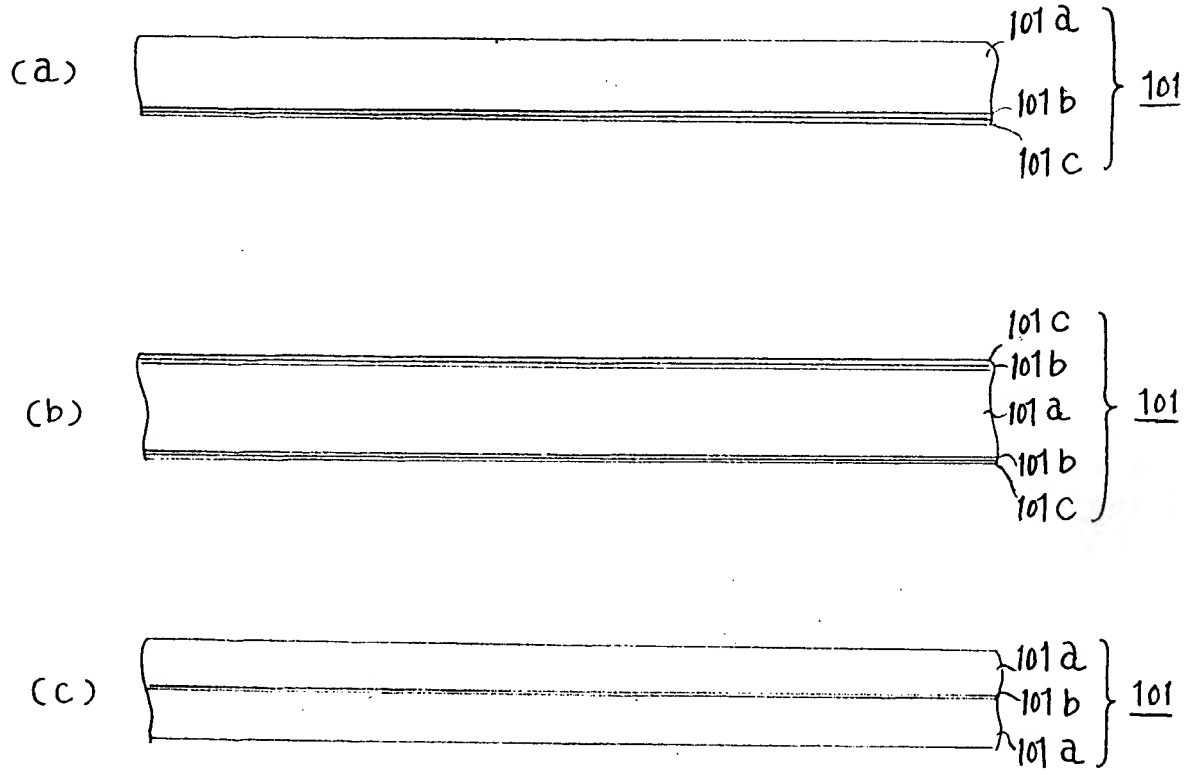

(a)
101a
101b
101c
101
(b)
101c
101b
101a
101b
101c
101
(c)
101a
101b
101a
101

Fig 10

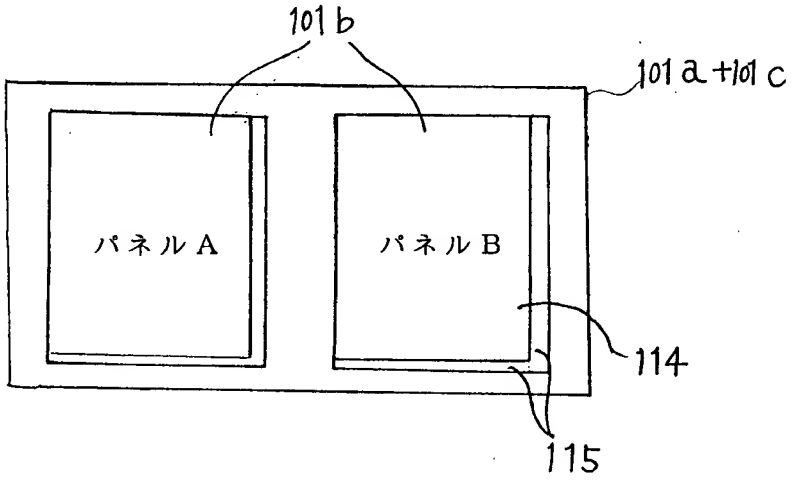

101b
101a+101c
パネルA
パネルB
114
115

Fig 11

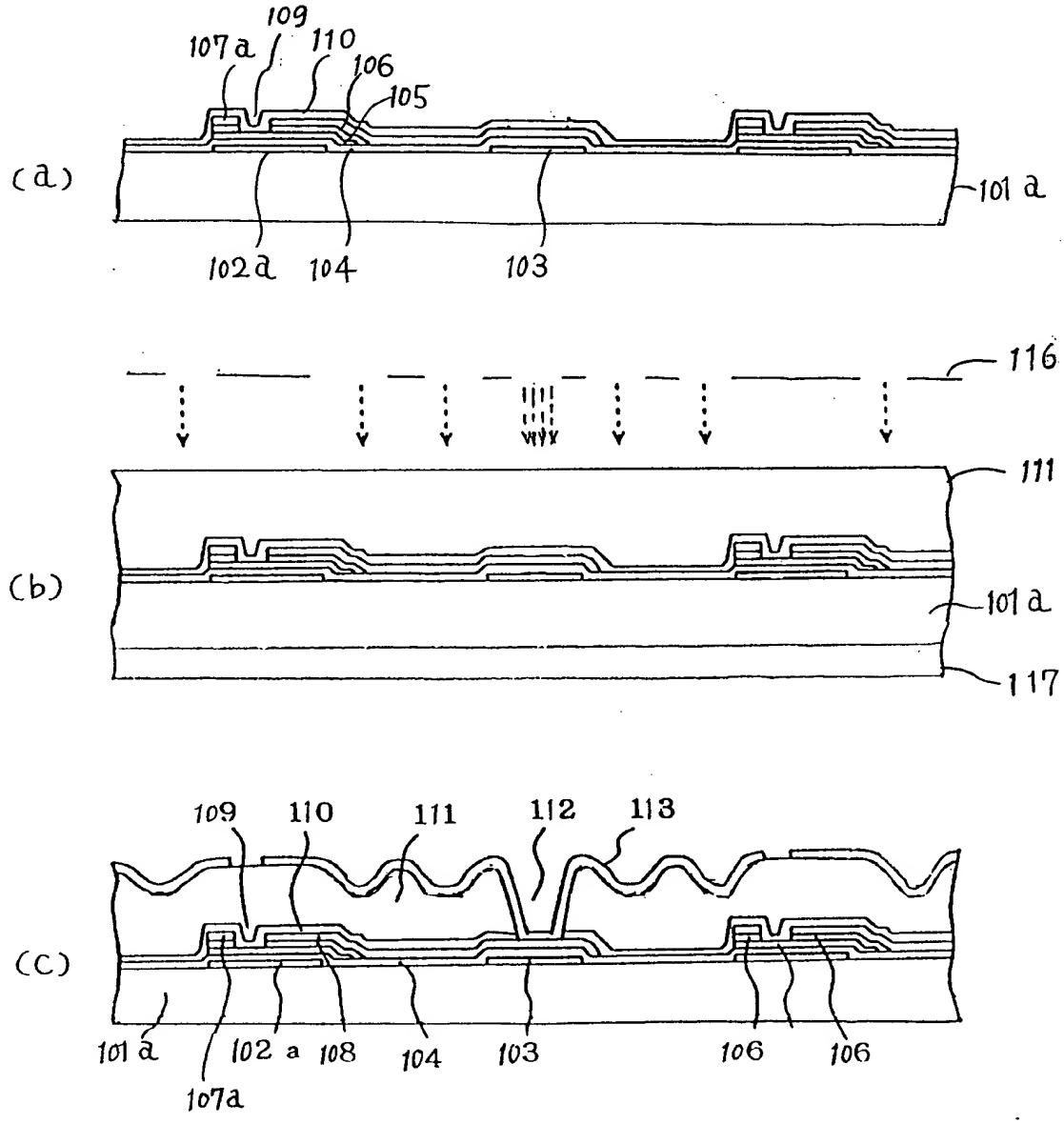

(a)
109
107a
110
106
105
101a
102a
104
103
116
(b)
111
101a
117
(c)
109
110
111
112
113
101a
107a
102a
108
104
103
106
106

Fig 12

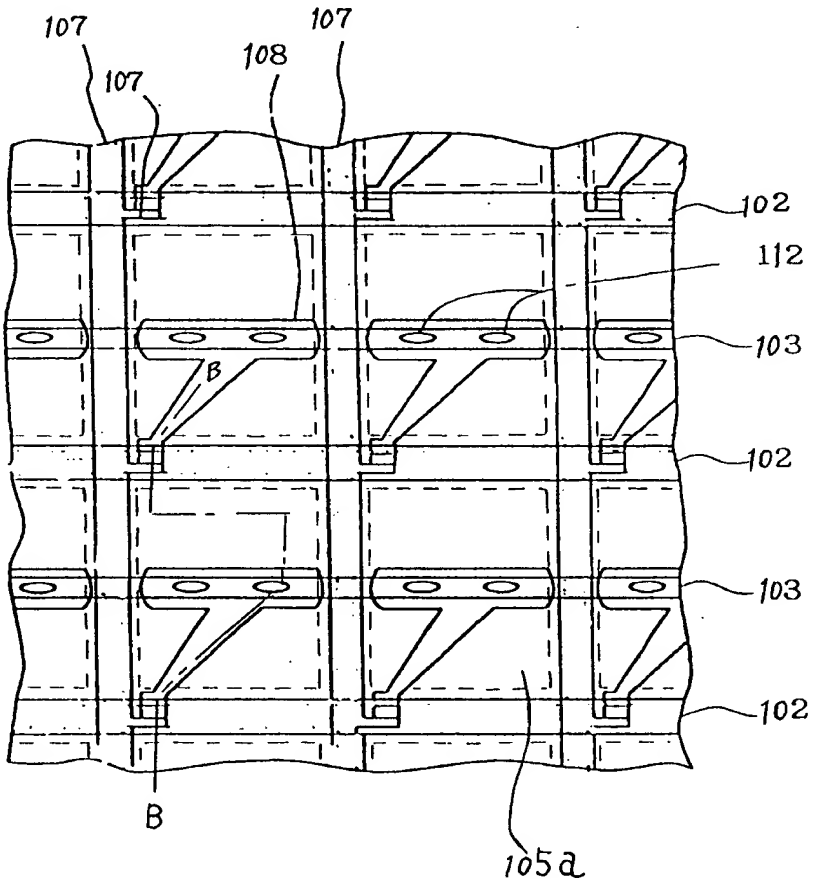


Fig 13

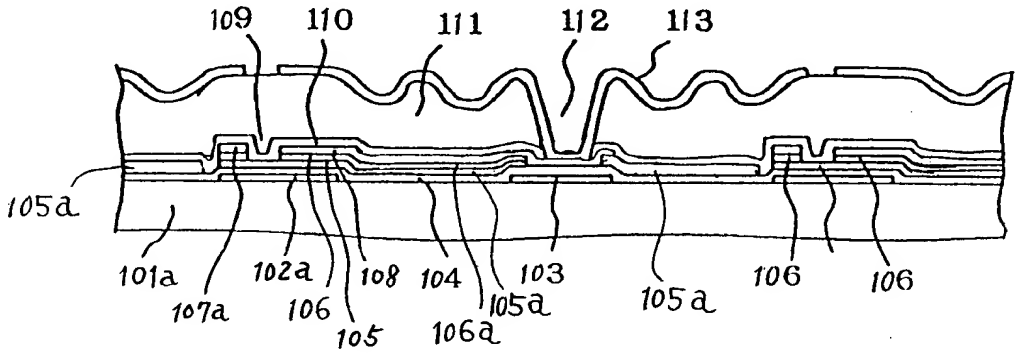

109
110
111
112
113
105a
101a
107a
102a
106
105
108
104
106a
105a
103
105a
106
106

Fig 14